## **REFERENCE LIST**

## **SEMICONDUCTOR**

SOLAR

PHARMA

POWER GENERATION

FOOD & BEVERAGE

PULP AND PAPER

CHEMICAL

OIL AND GAS

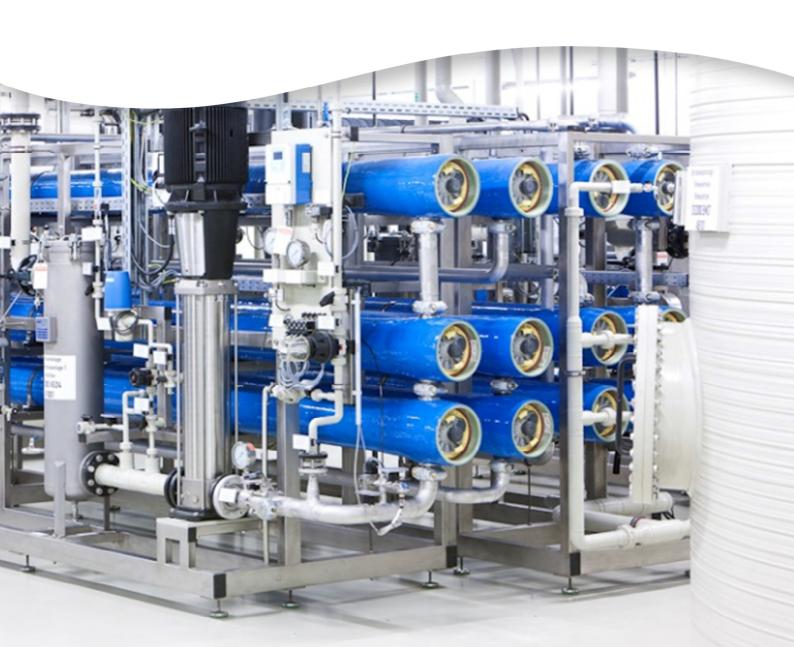
MINING

AEROSPACE AND TRANSPORT



## Ultrapure Water Production

Semiconductor and Electronic Industries



Client	Plant Type	Capaci	ity
Sunicon Freiberg/Germany	Water treatment for the photovoltaic industry	5	m³/h
Freiberg/Germany	Activated carbon filter, Softening, reverse osmosis, EDI		m³/h
Astex Berlin/Germany	Ultrapure water for the semiconductor industry Softening, ROCEDIS (reverse osmosis, EDI), tank, polishing mixed bed	1 x 0.6	m³/h
Mikron Selenograd/Russia	Extension of ultra pure water plant for semiconductor industry		
	Pre treatment + Make-up Heater, ultrafiltration, membrane degassing, ROCEDIS(reverse osmosis, EDI), UV-oxidation, ion exchanger with boron selective resin	15	m³/h
	Polishing UV-oxidation, cooler, mixed bed polisher, membrane degassing, ultrafiltration	25	m³/h
Epcos	Ultrapure water for the semiconductor industry		
Munich/Germany	ECOSOFT (softening), ROCEDIS (reverse osmosis, EDI), tank, UV-oxidation, polishing mixed bed	1 x 12	m³/h
ABB Lenzburg/Switzerland	Extension of ultra pure water plant for semiconductor Polishing Mixed bed, cooler, UV-oxidation, ultrafiltration	85	m³/h
	Overhaul pre treatment + Make-up	2 x 6	m³/h
CNII Mechaniki Moscow/Russia	Water treatment for the semiconductor industry  Pre treatment  Multi-media filter, activated carbon filter, reverse osmosis, EDI	1	m³/h
	Polishing UV, cooler, mixed bed, ultrafiltration	3	m³/h
ABB	Extension of ultra pure water plant for semiconductor		
Lenzburg/Switzerland	Pre treatment + Make-up ECOSOFT- Softening, reverse osmosis, UV-oxidation, membrane degasser, EDI	2 x 10	m³/h
Stangl	Water treatment for the photovoltaic industry		
Eichenau/Germany	Pre treatment + Make-up Softening, ROCEDIS, membrane degasier Polishing und Reclaim		m³/h m³/h
Deutsche Solar	UV-sanitising, mixed bed, end filter Water treatment for the photovoltaic industry		
Freiberg/Germany	Raw water treatment Ultrafiltration, activated carbon filter, UV	110	m³/h
	Cooling water treatment Filter, UV Demineralisation plant	150	m³/h
	Softener, Reverse Osmosis, UV, EDI, Polishing  Waste water treatment	85	m³/h
	Neutralisation	85	m³/h

1E600 Semicon UPW Rev 10 Page: 2 Of: 13 Date: 29/10/2015

Client	Plant Type	Capacity
Solibro GmbH Fab 2 Thalheim/Germany	UPW – production, recycling and wastewater treatment plant for photovoltaic industry	Not disclosed
ABB Lenzburg/Switzerland	Extension of ultra pure water plant for semiconductor Tank, pumps and extension of polishing system	18 m³/h
X/Fab Erfurt/Germany	Renewing of raw water pumps Exchange of pumps Including electrical installation	50 m³/h
Elmos Dortmund/Germany	Ultrapure water for semiconductor industry	10 m³/h
	RO, membrane degasser, EDI, UV, mixed bed polisher, cartridge filter	
lmec Leuven/Belgium	Ultrapure water for semiconductor industry	18 m³/h
	Extension of an ultrapure water plant EcoSoft, RO, membrane degasser, EDI UV, mixed bed polisher, ultrafiltration	12 m³/h
Osram Penang/Malaysia	Ultra pure water for semiconductor industry:	30 m³/h
	EcoSoft (Softener), RO, EDI, mixed bed polisher, UPW tank, UV, cartridge filter	
PETec Sedgefield/UK	Ultrapure water for semiconductor industry	0.5 m³/h
	EcoSoft (Softener), heat exchanger, Rocedis (RO, Membrane Degasser, EDI) SemiCircle (UV, Heat Exchanger, Mixed Bed, Ultrafiltration)	1.5 m³/h
Solibro Thalheim/Germany	Ultrapure water for solar industry	Not disclosed
Solon	Ultrapure water for solar industry	
Berlin/Germany	Softening, activated carbon filter, heat exchanger ROCEDIS (RO, Membrane Degasser, EDI)	1.0 m³/h 1.5
Vector / HP	SEMICIRCLE (UV, Mixed Bed, Ultrafiltration)  Modification of the ultra pure water system	m³/h
Dublin/Republic of Ireland	Ecosoft (Softening) Membrane degasser	45 m³/h 40
X-Fab	Extension of ultra pure water system	m³/h
Erfurt/Germany	Dosing, Reverse osmosis	18 m³/h
Epcos München/Germany	Ultrapure water for semiconductor production Refurbishment of EDI System	12
минывиленнану	Neturnatinent of Edi System	m <sup>3</sup> /h

1E600 Semicon UPW Rev 10 Page: 3 Of: 13 Date: 29/10/2015

Client	Plant Type	Capaci	ity
Infineon Villach/Austria	Ultrapure water for semiconductor production Tank, heat exchanger, decarbonisation, membrane degasser, reverse osmosis, Tank, UV oxidation, external regenerable mixed bed, Polishing: Tank, UV-oxidation, cooler, mixed bed polisher, ultrafiltration		80 m³/h 80
Plastic Logic Dresden/Germany	Ultrapure water for semiconductor production ECOSOFT (Softener), heat exchanger, ROCEDIS (RO, Membrane Degasser, EDI) SEMICIRCLE (UV, Heat Exchanger, Mixed Bed, Ultrafiltration)		m³/h  15 m³/h 30
Nivarox Neuchâtel/Switzerland	Ultrapure water for micro-mechanic applications ROCEDIS (RO, Membrane Degasser, EDI) SEMICIRCLE (UV, Mixed Bed, Filtration)	6	m <sup>3</sup> /h m <sup>3</sup> /h 10 m <sup>3</sup> /h
Mikron Selenograd/Russia	Ultrapure water for semiconductor production Heater, Ultrafiltration, Novalis (RO), Membrane Degasser, ROCEDIS (RO, UV Oxidation, EDI) SEMICIRCLE (UV Oxidation, Cooler, Mixed Bed, Membrane Degasser, Ultrafiltration)		15 m³/h 30
Epcos München/Germany	Ultrapure water for semiconductor production ECOSOFT (Softener), ROCEDIS (RO, Membrane Degasser, EDI) SEMICIRCLE (UV Oxidation, Mixed Bed, Filtration)		m <sup>3</sup> /h  13  m <sup>3</sup> /h  20
Bosch Reutlingen/Germany	Extension of Ultrapure water semiconductor production Membrane Degasser	2 x 37	m³/h m³/h
Photovoltech Tienen/Belgium	Ultrapure water for solar cell production ECOSOFT (Softening), ROCEDIS (Reserve Osmosis, EDI) UV-disinfection, mixed bed polisher, final filters		15 m³/h 10 m³/h 16
Bosch Reutlingen/Germany	Extension of Ultrapure water semiconductor production MB, Regeneration station, UV, Final Filters	150	m³/h m³/h
ST Microelectronics Tours/France	Extension of Ultrapure water for semiconductor production Polishing mixed bed exchanger	70	m³/h
AMS Graz/Austria	Extension of Ultrapure water for semiconductor production  Multimedia filter, activated carbon filter, demineralisation with ion exchangers, reverse osmosis, UV oxidation, membrane degasser, mixed bed ion exchange		m³/h

1E600 Semicon UPW Rev 10 Page: 4 Of: 13 Date: 29/10/2015

Client	Plant Type	Capacity
ST Microelectronics Singapore	Ultrapure water for semiconductor production Make up: Membrane degasser, UV, EDI, Mixed Bed, UPW Tank, Polishing: UV oxidation, Cooler, Mixed Bed, MDG, UF, Loop	50 m³/h 40 m³/h 100 m³/h
Fraunhofer Institut IPMS Dresden/Germany	Ultrapure water for semiconductor production ECOSOFT (Softening), ROCEDIS (Reserve Osmosis, MDG, EDI) UV-oxidation, mixed bed polisher, ultrafiltration Humidifier supply	25 m³/h 2 x 5 m³/h 15 m³/h 1
AMIS Oudenaarde/Belgium	Extension of an ultrapure water plant ECOSOFT (Softening) EDI	40 m³/h 2 x 15 m³/h
Atmel Newcastle/UK	Ultrapure water for semiconductor production Ultrafiltration	2 x 7 m³/h
Infineon Porto/Portugal	Extension of an ultrapure water plant Multimedia Filter, ECOSOFT (Softening), ROCEDIS (Reserve Osmosis, EDI) UV-oxidation, mixed bed polisher, ultrafiltration	10 m³/h 7 m³/h 10 m³/h
SEZ AG Villach/Austria	Ultrapure water for semiconductor production ECOSOFT (Softening), ROCEDIS (Reserve Osmosis, MDG, EDI) UV-oxidation, mixed bed polisher, ultrafiltration Humidifier supply	1.2 m³/h 4 m³/h 1
AMIS Oudenaarde/Belgium	Ultrapure water for semiconductor production Replacement of a vacuum degasser by membrane degasser	m³/h 35 m³/h
APZ Illmenau Illmenau/Germany	Ultrapure water for semiconductor production Extension of UPW plant ECOSOFT (Softening), ROCEDIS (Reserve Osmosis, MDG, EDI) New Polishing System UV-oxidation, mixed bed polisher, ultrafiltration	6 m³/h 40 m³/h
Fraunhofer Institut Freiburg Freiburg/Germany	Ultrapure water for semiconductor production ECOSOFT (Softening), ROCEDIS (Reserve Osmosis, MDG, EDI), mixed bed polisher, UV-oxidation, mixed bed polisher, ultrafiltration	5 m/³h

1E600 Semicon UPW Rev 10 Page: 5 Of: 13 Date: 29/10/2015

Plant Type	Capacity
Ultrapure water for semiconductor production	
ECOSOFT (Softening), ROCEDIS (reserve osmosis, EDI),	10
UV-oxidation, mixed bed polisher, cartridge filter	m³/h
Ultrapure water for semiconductor production	
Petrofitting and extension:	
Softening, reserve osmosis, EDI, UV-oxidation,	20
mixed bed, polisher, cartridge filter	m³/h
Neutralisation	35
	m³/h
Ultranura water for semiconductor production	
Raw water-Ultrafiltration for surface water, ACF, double pass	80
reverse osmosis, membrane degasser, UV-oxidation,	m³/h
regenerable mixed bed, UPW tank, UV-oxidation, mixed bed	
polisher, membrane degasser, ultrafiltration	
Ultrapure water for semiconductor production	
Make up system with : Activated carbon filter,	50
Decarbonisation, atmospheric degasser, double pass reverse osmosis, UV-oxidation, working mixed bed	m³/h
Ultrapure water for semiconductor production	
ECOSOFT (Softening), ROCEDIS (Reserve Osmosis,	1.2
MDG, EDI)	m³/h
UV-oxidation, mixed bed polisher, ultrafiltration	4
	4 m³/h
Ultrapure water for semiconductor production	
Extension of EDI-System	52 m³/h
Ultrapure water for semiconductor production	
Extension of HOT-DI- System	10 m³/h
Supervision of commissioning of Ultrapure Water Plant	
Ultrapure water for semiconductor production	
Softener Ecosoft, reverse osmosis, EDI, mixed bed	30 m³/h
polisher, UPW tank, UV-sterilisation, mixed bed polisher, cartridge filter	
Tank, UV sterilisation, polisher mixed bed exchanger, ultrafiltration	60 m³/h
Ultrapure water for semiconductor production	
Cation evaluation membrane degrades reverse comesia	80 m³/h
Cation exchanger, membrane degasser, reverse osmosis,	00 111711
CONTIPUR (CEDI), mixed bed polisher	00 III /II
	Ultrapure water for semiconductor production ECOSOFT (Softening), ROCEDIS (reserve osmosis, EDI), UV-oxidation, mixed bed polisher, cartridge filter  Ultrapure water for semiconductor production Retrofitting and extension: Softening, reserve osmosis, EDI, UV-oxidation, mixed bed, polisher, cartridge filter Neutralisation  Ultrapure water for semiconductor production Raw water-Ultrafiltration for surface water, ACF, double pass reverse osmosis, membrane degasser, UV-oxidation, regenerable mixed bed, UPW tank, UV-oxidation, mixed bed polisher, membrane degasser, ultrafiltration  Ultrapure water for semiconductor production Make up system with: Activated carbon filter, Decarbonisation, atmospheric degasser, double pass reverse osmosis, UV-oxidation, working mixed bed  Ultrapure water for semiconductor production ECOSOFT (Softening), ROCEDIS (Reserve Osmosis, MDG, EDI) UV-oxidation, mixed bed polisher, ultrafiltration  Ultrapure water for semiconductor production Extension of EDI-System  Ultrapure water for semiconductor production Extension of HOT-DI- System  Supervision of commissioning of Ultrapure Water Plant  Ultrapure water for semiconductor production Softener Ecosoft, reverse osmosis, EDI, mixed bed polisher, ultrafilter production Softener Ecosoft, reverse osmosis, EDI, mixed bed polisher, cartridge filter  Ultrapure water for semiconductor production Tank, UV sterilisation, polisher mixed bed exchanger,

1E600 Semicon UPW Rev 10 Page: 6 Of: 13 Date: 29/10/2015

Client	Plant Type	Capaci	ty
FUBA Printed Circuits GmbH Gittelde/Germany Chartered Semiconductor Manufacturing Singapore	Process water for the electronics industry Upflow solid bed plant, tank, mixed bed exchanger Ultrapure water for semiconductor production Polishing ultrafiltration	2	m³/h m³/h m³/h
Hewlett Packard Dublin/Republic of Ireland	Ultrapure water for the production of printer cartridges: Multimedia filter, softening, CONTIPUR (CEDI)	27	m³/h
DuPont Photomask Inc. Corbeil Essonnes/France	Ultrapure water for a sub-supplier of semiconductor production Polishing system: UV, mixed bed polisher, ultrafiltration	6	m³/h
X-Fab Erfurt/Germany	Ultrapure water production for semiconductor production Dosing stations, 4 reverse osmosis plants Novalis, ContiPur (CEDI), mixed bed polisher, UPW tank, UPW pumps	30	m³/h
Epcos Singapore	Ultrapure water for semiconductor production Extension of an existing treatment plant, CONTIPUR (CEDI), mixed bed polisher	3.5	m³/h
Wacker Siltronic Burghausen/Germany	Ultrapure water for semiconductor production Extension of an existing treatment plant, reverse osmosis, UV oxidation, mixed bed polisher, ultrafiltration	15	m³/h
	Loop	30	m³/h
AMS Graz/Austria through	Ultrapure water for semiconductor production Multimedia filter, activated carbon filter, demineralisation with ion exchangers, reverse osmosis, UV oxidation, membrane degasser, mixed bed exchanger	28	m³/h
Siegle + Epple	UPW tank, heat exchanger, UV oxidation, mixed bed polisher, ultrafiltration Loop	75	m³/h
Bosch Reutlingen/Germany	Ultrapure water for semiconductor production Extension of an existing demineralisation system	35	m³/h
Facility Service GmbH Heilbronn/Germany	Ultrapure water for semiconductor production Mixed bed polisher, UV, filter	5	m³/h
Infineon Burgweinting/Germany	Ultrapure water production for and treatment of wastewater resulting from semiconductor production (back end):		
	Softening reverse osmosis, ContiPur (CEDI) Loop: mixed bed polisher	12	m³/h
	Continuous neutralisation, lift stations	12	m³/h
CS2 Kortenberg/Belgium	Ultrapure water for semiconductor production Softening, activated carbon filter, reverse osmosis, membrane degasser, CONTIPUR (CEDI)	13.2	m³/h
L. C	Loop	10	m³/h
Infineon Dresden/Germany	Ultrapure water for semiconductor production Raw water ultrafiltration, activated carbon filter, softener, double-pass reverse osmosis, UV oxidation, membrane degasser, externally regenerated mixed bed exchanger	80	m³/h
	UPW tank, heat exchanger, UV oxidation, mixed bed polisher, ultrafiltration		

1E600 Semicon UPW Rev 10 Page: 7 Of: 13 Date: 29/10/2015

Client	Plant Type	Capacity
TECH Singapore	Ultrapure water production and TMAH dosing Dosing plant, DI tank, filter	1.25 m³/h
Mitsubishi Alsdorf/Germany	Ultrapure water for semiconductor production Demineralisation with ion exchanger, mixed bed exchanger, vacuum degasser, reverse osmosis plant	118 m³/h
	Loop	63 m³/h
Varioplan La Neuveville/Switzerland	Pure water for electronics and semiconductor production DI water plant, neutralisation	0.5 m³/h
Philips Nijmegen/Netherlands	Ultrapure water for semiconductor production Polishing system: reverse osmosis, membrane degasser, mixed bed polisher, ultrafiltration Loop	60 m³/h
		(60 m³/h)
1 <sup>st</sup> Silicon Kuching/Malaysia	Ultrapure water for the 8" wafer production Multimedia filter, activated carbon filter, decarbonisation, double-pass reverse osmosis plant, vacuum degasser, externally regenerated mixed bed exchanger	160 m³/h
	Polishing system: UV oxidation, membrane degasser, polisher mixed bed exchanger, ultrafiltration Loop	
		2 x 120 m³/h
MIMOS Semiconductor Kuala Lumpur/Malaysia	Ultrapure water for semiconductor production Extension of an already existing UPW system by a membrane degasser stage	23 m³/h
TEMIC-FSG Heilbronn/Germany	Ultrapure water for semiconductor production TOC UV system, anion polisher, mixed bed polisher	5 m³/h
Infineon Technologies Regensburg/Germany	Ultrapure water for semiconductor production Extension 1: decarbonisation, vacuum degasser	25 m³/h
	Extension 2: decarbonisation, reverse osmosis, membrane degasser, UV, mixed bed exchanger	50 m³/h
	Extension 3: UV, polisher, ultrafiltration, reject ultrafiltration	80 m³/h
	Quality improvement: ultrafiltration, reject ultrafiltration	43 m³/h
Infineon Technologies Dresden/Germany	Ultrapure water for semiconductor production Extension of pre-treatment/make-up	90 m³/h
	Extension of UPW tanks	2 x 120 m³/h
IBM Corbeil/France	Ultrapure water for semiconductor production Reverse osmosis	5 x 30 m³/h
Merck Schuchardt Hohenbrunn/Germany	Pure water for the electronics industry: Softening, reverse osmosis Novalis, membrane degasser	0.5 m³/h
IMEC Leuven/Belgium	Ultrapure water for semiconductor production Softening, reverse osmosis, UV oxidation, CONTIPUR (CEDI), mixed bed polisher Polishing system: UPW tank, UV oxidation, membrane degasser, heat exchanger, mixed bed polisher, ultrafiltration	20 m³/h
Mitsubishi	Ultrapure water for semiconductor production	
Alsdorf/Germany	Supply of CMP process with ultrapure water via UPW loop, the UPW water being produced by an already existing H+E system	11 m³/h
1E600 Semicon UPW Rev 10	Page: 8 Of: 13	Date: 29/10/2015

Client	Plant Type	Capaci	ity
Tech Singapore	Ultrapure water for semiconductor production UPW tank, pump, UV, TMAH dosing	18	m³/h
Clariant GmbH Wiesbaden/Germany	Ultrapure water for the production of fine chemicals Reverse osmosis, membrane degasser, UV, mixed bed exchanger, fine filter	5	m³/h
Clariant GmbH Wiesbaden/Germany	Ultrapure water for the production of fine chemicals Polishing line consisting of UV, mixed bed exchanger, fine filter	15	m³/h
Videoton Szekesfeh/Hungary	Ultrapure water for semiconductor production Prefiltration, reverse osmosis, CONTIPUR (CEDI), membrane degasser, tank, mixed bed polisher, tank	9.5	m³/h
Unibauamt Freiburg/Germany	Ultrapure water for the semiconductor research Pre-filtration, softening, heat exchanger, membrane degasser, reverse osmosis, CONTIPUR (CEDI)	5	m³/h
	Tank, mixed bed polisher, loop		
	Neutralisation		
LGM Böblingen/Germany	Filtration, UV, filtration  Ultrapure water for semiconductor production  Replacement of existing reverse osmosis system by a two- stage permeate-staged reverse osmosis system for desalination, TOC reduction and removal of boron, equipped with low pressure modules	4 x 25	m³/h
Bosch Reutlingen/Germany	Ultrapure water for semiconductor production Pre-filtration, ultrafiltration, tank	150	m³/h
CS2 Zaventem/Belgium	Ultrapure water for the semiconductor finishing Activated carbon filter, softener, reverse osmosis, membrane degasser, ContiPur (CEDI)	4.5	m³/h
	Tank, sterile filter, heat exchanger,		
Sunways	Loop Ultrapure water production and wastewater treatment for	6	m³/h
Konstanz/Germany	the production of solar cells Pre-filtration, reverse osmosis, CONTIPUR (CEDI), ultrapure water tank	max. 16.4	m³/h
	Continuous neutralisation	max. 16.4	m³/h
	Reclaim		m³/h
EUPEC Pretzfeld/Germany	Ultrapure water for the thyristor production Softening, reverse osmosis, CONTIPUR (CEDI)		m³/h
	UV, mixed bed polisher, fine filtration		
Heidenhain Traunreut/Germany	Ultrapure water for the production of tools: CONTIPUR (CEDI)	9	m³/h
Ericsson Kista/Sweden	Ultrapure water for semiconductor production UV, mixed bed exchanger, ultrafiltration	20	m³/h

1E600 Semicon UPW Rev 10 Page: 9 Of: 13 Date: 29/10/2015

Client	Plant Type	Capacit	ty
Mietec Oudenaarde/Belgium	Ultrapure water for semiconductor production  Extension of reclaim system		
	Tank, dosing unit, three-stage reverse osmosis	8	m³/h
	Tank, filter, reverse osmosis, UPW tank	4.5	m³/h
	Tank, mixed bed polisher	8	m³/h
Polygram Langenhagen/Germany	Ultrapure water for the CD production: Cation exchanger, anion exchanger, UV, mixed bed exchanger, fine filter	8	m³/h
University Lausanne/Switzerland	Ultrapure water for cleanroom technique Tank, ContiPur (CEDI)	4	m³/h
	Tank, UV, mixed bed polisher, fine filtration		
IBM Deutschland GmbH Böblingen/Germany	Treatment of HF-containing rinsing water Activated carbon filter, ion exchanger, bio-filter, ozone/UV treatment	10	m³/h
Shin Etsu Handotai Livingston/UK	Expansion of an existing Ultrapure water for the semiconductor production Turbidity removal filter, activated carbon filter, degasser, reverse osmosis, mixed bed polisher, UV sterilisation, 2 <sup>nd</sup> reverse osmosis, final polisher and ultra filtration UPW (phase 1 + 2) DW (phase 1 +2)		62 m³/h 45 m³/h
ABB Lenzburg/Switzerland	Ultrapure water for the BMOS production: Softener, reverse osmosis plant, CONTIPUR (CEDI)		m³/h
	Mixed bed polisher, ultrafiltration  Wastewater treatment plant, chemical dosing systems		
Wacker Chemie Burghausen/Germany	Ultrapure water for the 12" wafer production: Reverse osmosis plant, UV oxidation, mixed bed polisher, ultrafiltration	15	m³/h
	Loop	40	m³/h
Siemens/Matsushita Singapore	Production of ultrapure water  Multimedia filter, softener, reverse osmosis plant, mixed bed exchanger, UV oxidation, mixed bed exchanger cartridges	3	m³/h
Chartered Semiconductor Manufacturing Pte. Ltd Singapore 40K Extension	Ultrapure water for the 16/64 MB production Reverse osmosis plant, vacuum degasser, catalytic oxygen removal, externally regenerated mixed bed exchanger, polisher reverse osmosis plant, UV oxidation, various mixed bed polishers, ultrafiltration	74	m³/h
	Loop	112	m³/h
Chartered Semiconductor Manufacturing Pte. Ltd Singapore 30% Extension	Ultrapure water for the 16/64 MB production Reverse osmosis plant, vacuum degasser, catalytic oxygen removal, externally regenerated mixed bed exchanger, polisher reverse osmosis plant	48	m³/h
Siemens Microelectronic North Tyneside Tyne and Wear UK through	Ultrapure water for the 8" wafer production Reverse osmosis plant I, vacuum degasser, UV oxidation, externally regenerated mixed bed exchanger, reverse osmosis plant II, UV oxidation, mixed bed polisher, ultrafiltration, hot DI, DI reclaim	120	m³/h
McAlpine-Hochtief JV			

1E600 Semicon UPW Rev 10 Page: 10 Of: 13 Date: 29/10/2015

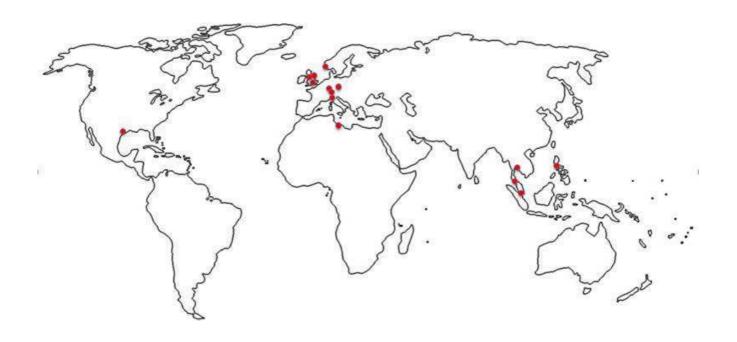
Client	Plant Type	Capaci	ity
Mitsubishi Semiconductor Europe Alsdorf/Germany	Extension of an existing plant for the production of ultrapure water for semiconductor production Vacuum degasser, polisher plant with UV oxidation, polisher anion exchanger, UV oxidation, mixed bed polisher, ultrafiltration	55	m³/h
	Extendable to a capacity of	115	m³/h
SIMEC GmbH Dresden/Germany	This extension also comprises a DI reclaim plant.  Ultrapure water for the 16/64 MB production - Modules 1 and 2  Each with reverse osmosis plant, vacuum degasser, catalytic	2 x 120	m³/h
	oxygen removal externally regenerated mixed bed exchangers, polisher reverse osmosis plant, UV oxidation, various ion exchange polishers, ultrafiltration, hot DI		
	DI-reclaim, loop and equipment connections	2 x 140	m³/h
	Loop - modules 1 and 2 Wastewater treatment - modules 1 and 2 DI reclaim ( > 70 %) - module 1		m³/h m³/h
Chartered Semiconductor Manufacturing Pte. Ltd Singapore	Ultrapure water for the 16/64 MB production Reverse osmosis plant, vacuum degasser, catalytic oxygen removal, externally regenerated mixed bed exchanger, polisher reverse osmosis plant, UV oxidation, various mixed bed polishers, ultrafiltration	74	m³/h
	Loop	112	m³/h
Shin Etsu Handotai Livingston/UK	Ultrapure water for the semiconductor production Turbidity removal filter, activated carbon filter, degasser, reverse osmosis, mixed bed polisher, UV sterilisation, 2 <sup>nd</sup> reverse osmosis, final polisher and ultra-filtration UPW (phase 1) DW (phase 1)		42 m³/h 33 m³/h
Ericsson AB Kista/Sweden	Ultrapure water for the 64 MB production Reverse osmosis plant, vacuum degasser, externally regenerated mixed bed exchanger, polisher reverse osmosis plant, UV oxidation, various mixed bed polishers, ultrafiltration	15	m³/h
Wacker Chemie Burghausen/Germany	Ultrapure water for the wafer production Ultrafiltration, externally regenerated mixed bed exchanger with IR-PVDF piping, UV sterilisation, fine filter	40	m³/h
Wacker Chemie GmbH Burghausen/Germany	Ultrapure water production systems of various sizes Most of them being reverse osmosis plants in combination with ultrafiltration	30	m³/h
Alcatel Mietec Oudenaarde/Belgium	Ultrapure water for the wafer production Reverse osmosis plant, vacuum degasser, externally regenerated mixed bed exchanger, polisher reverse osmosis plant, UV sterilisation, mixed bed polisher, ultrafiltration, loop and equipment connections	22	m³/h
ANT Backnang/Germany	Ultrapure water for a research laboratory Softener, permeate-staged reverse osmosis plant, mixed bed polisher	2	m³/h
	Loop (free from grooves)	5	m³/h
Telefunken Heilbronn/Germany	Water for the semiconductor production Reverse osmosis plant (fed with 18 MOhm ultrapure water from an already existing plant), three mixed bed polishers	8.3	m³/h

1E600 Semicon UPW Rev 10 Page: 11 Of: 13 Date: 29/10/2015

Client	Plant Type	Capaci	ity
IBM Deutschland GmbH Böblingen-Hulb/Germany	Ultrapure water production plant Reverse osmosis plant, mixed bed exchanger, polishing stages, non-regenerable mixed bed polisher, connection of the individual units via tube channel having a length of about 500 m, with downstream polishing stage	150	m³/h
IBM Deutschland GmbH Sindelfingen/Germany	Ultrapure water production plants of various sizes		
	Mostly ion exchange Wastewater treatment, wastewater desalination Recovery of copper and EDTA resulting from CC4 processes, DI reclaim, polishing stages, selective ion exchanger	up to 200	m³/h
University of Erlangen-Nürnberg Technologiegebäude Mikroelektronik Erlangen/Germany	Ultrapure water for a semiconductor research laboratory H decarbonisation, reverse osmosis plant, vacuum degasser, regenerable mixed bed exchanger, pure water station, mixed bed polisher, UV sterilisation, sterile filter and ultrafiltration	10	m³/h
	Wastewater treatment plant for the disposal of water and regenerates resulting from lab baths		
IBM Deutschland GmbH Sindelfingen/Germany	Production of high-quality rinsing water Ultrafiltration plant for the removal of particles and bacteria from DI water	39	m³/h
Mitsubishi Semiconductor Europe Alsdorf/Germany	Ultrapure water for the semiconductor production Fluidised bed ion exchanger, reverse osmosis plant, vacuum degasser, externally regenerated mixed bed exchangers, ozonisation and UV sterilisation	55	m³/h

1E600 Semicon UPW Rev 10 Page: 12 Of: 13 Date: 29/10/2015

H+E ranks among the world's leading suppliers in the fields of: water & wastewater treatment, and energy efficiency. Based on its global presence, the H+E GROUP has completed projects in over 50 countries.





Tel: +44 1403 272772

sales@he-water.co.uk www.he-water.co.uk